TRANSMITTALLETTER					DOCKET NO. MICR155		
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SERIAL NO.	FILI	NG DATE	EXAMINER Whipple, Matthe			GROUP ART UNIT 1104	
08/636,069	DEC 0 1 1107 PT	22, 1996			ew		
INVENTOR(S)	2						
INVENTION:		educe Fi	ixed Charge I	n CVD O	zon De	posited File	ms
TO THE COM	MISSIONER OF	PATENTS	AND TRADEMA	RKS:			
	Transmitted	l herewith i	s an amendment	in the abo	ve-identifie	ed application.	المحجم فالدراء سيدران رارا
		The fee	has been calcula			1.	RECEIVED
1	*2*	*3*	*4*	*5*	*6*		*7* DEC 1 9 1997
			•	No. of Extr	ra		DEC 18,1997
	Claims Remaining After Amendment		Highest Number Previously Paid For	Claims Present	Rat	•	Additional
	* 30	MINUS	** 24	- 6 -	X \$22		Fee \$ - 132.00 -
TOTAL CLAIMS							
INDEP. CLAIMS	* 6	MINUS	*** 3	- 3 -	X \$82		\$ - 246.00 -
				DITIONAL FI			\$ -378.00 -
			FOR THIS	S AMENDMEI	NT		
	ntry in column 2 is						
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*** If the "h	lighest Number P	reviously F	Paid For" IN THIS	SPACE is	less than	3, write "3" in t	his space.
☐No additi	ional fee is require	ed.					
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☐The under		-		_		•	er 34 CFR 1.136 and

20231 on: November 25, 1997.

(Signature of person mailing papers)

Margared M. Dunbar Attorney for Applicant(s)

Registration No. 37,818

Ormiston Korfanta Dunbar & Holland, P.L.L.C.

P.O. Box 1840

Boise, Idaho 83701-1840 voice: (208) 336-1234

fax: (208) 336-8344

DEC 0 1 1997

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

#5/a mR 12/24/97

In re Application of:

Sandhu, Gurtej

Serial number:

08/636,069

Filed:

4/22/96

Group Art Unit:

1104

Examiner:

Matthew Whipple

Title:

Method To Reduce Fixed Charge In

CVD Ozone Deposited Films

RESPONSE TO OFFICE ACTION

Mailed: 08/18/97

<u>AMENDMENT A</u>

COMMISSIONER OF PATENTS AND TRADEMARKS Box Fee Amendment Commissioner of Patents and Trademarks Washington, DC 20231

Dear Sir:

In response to the Office Action mailed August 18, 1997, please enter the following amendments and remarks of record.

IN THE SPECIFICATION

On page 6, line 3, after "volume." please insert the sentence—The term substrate refers to one or more semiconductor layers or structures which includes active or operable portions of semiconductor devices. —

On page 6, line 6, after "reaction" please insert -- volume of gas, above the --.

On page 8, line 3, after the word "turn" please delete the word "will".

RESPONSE TO OFFICE ACTION SN 08/636,069

Page 1 of 10 Amendment A